

[ABSTRACT]

A resist composition containing a resin (A), an acid generator (B), and a crosslinking agent (C), in which the resin (A) is an alkali-soluble resin having a molar absorption coefficient of $2,000 \text{ mol}^{-1} \cdot \text{L} \cdot \text{cm}^{-1}$ or less at a wavelength of 248 nm, and the

5 crosslinking agent (C) is at least one crosslinking agent selected from the group consisting of a melamine-based crosslinking agent, a urea-based crosslinking agent, an alkylene urea-based crosslinking agent, a glycoluril-based crosslinking agent, and an epoxy-based crosslinking agent.